

# SPC in practice, control charts with runs rules, and EWMA

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- 1 Introduction
- 2 Run Rules for control charts
- 3 Competitors and competition
- 4 Conclusions

## SPC

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- **Storm Prediction Center.**
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- **S**tatistical **P**rocess **C**ontrol.

- Change point detection.
- On-line monitoring.
- Surveillance.
- Disorder problems.
- Detection of abrupt changes.
- Jump detection.
- Fault detection (... FDC).
- ...

WOODALL/MONTGOMERY (1999),  
Research issues and ideas in statistical process control.  
*Journal of Quality Technology*, 31, 376-386

*... in the area of control charting and SPC. As a general definition, we include in this area any statistical method designed to detect changes in a process over time.*

# Elements of SPC

## 1 Scope

Statistical process control (SPC) concerns the use of statistical techniques and/or stochastic control algorithms to achieve one or more of the following objectives:

- a) to increase knowledge about a process;
- b) to steer a process to behave in the desired way;
- c) to reduce variation of final-product parameters, or in other ways improve performance of a process.

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- 3 misses the point: actually, SPC is deployed for checking stability – stability is currently a big topic in semiconductor industry,
- 4 does not fit to the usual understanding of the term (SPC = control charting).



- WOODALL (2000), Controversies and Contradictions in Statistical Process Control, *Journal of Quality Technology*, 32, 341-350.
- STOUMBOS/REYNOLDS JR./RYAN/WOODALL (2000), The state of statistical process control as we proceed into the 21st century, *J. Amer. Statist. Assoc.*, 95, 992-997.

# Opinions of my non-statisticians colleagues

- "SPC, that is the application of these sophisticated trend rules like 2 of 3",
- "my SPC is out of SPEC",
- "oh, this alarm is caused by a mask that should not be considered in that chart at all",
- "why should I use these  $3\sigma$  limits if I have no idea what to do after an alarm",
- "control charts should be generally handled by the cleanroom (= shop floor) personnel",
- ...

# Focus on Runs Rules Phenomenon

- ①  $p, \bar{X}$  control chart designed by SHEWHART (1924/31).
- ② Bayesian approach by GIRSHICK/RUBIN (1952).
- ③ CUSUM by PAGE (1954).
- ④ Runs Rules  
(PAGE 1955, Western Electric 1956, ROBERTS 1958, NELSON 1984).
- ⑤ EWMA (GMA) by ROBERTS (1959).

# Which charts are available in SPC software?

- WinSPC (AMTC): all flavours of Shewhart charts + large assortment of runs rules,
- SPACE (IFX,Qimonda[,Atmel, TOPPAN,ZMD,Samsung,ST]): Shewhart charts, runs rules, MA, EWMA,
- ASPECT (AMD): like WinSPC,
- ...

Given that  $\{X_i\}$  follows  $\mathcal{N}(\mu, \sigma^2)$ :

Flag if

- (Shewhart limits)  $|X_i - \mu_0| > 3\sigma$ ,
- (2 of 3) 2 of 3 succeeding  $X_i$  are  $\begin{cases} > \mu_0 + 2\sigma \\ < \mu_0 - 2\sigma \end{cases}$ ,
- (4 of 5) 4 of 5 succeeding  $X_i$  are  $\begin{cases} > \mu_0 + \sigma \\ < \mu_0 - \sigma \end{cases}$ ,
- (8 of 8) 8 of 8 succeeding  $X_i$  are  $\begin{cases} > \mu_0 \\ < \mu_0 \end{cases}$ .

# Fall and rise of Runs Rules control charts

- ① **Fall:** CHAMP/WOODALL (1987), Exact results for Shewhart control charts with supplementary runs rules, *Technometrics*, 29, 393-399

*It has been shown that supplementary runs rules cause the Shewhart chart to be more sensitive to small shifts in the mean, but not as sensitive as the CUSUM chart.*

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- 2 **Rise:** quality manuals & circles, SPC procedures etc. in practice, Current Index of Statistics: 8 papers in 2002 and newer (Quality Engineering, CSSC)

KLEIN (2000), Two alternatives to the Shewhart  $\bar{X}$  control chart, *JQT*, 32, 427-431.

YASUI/OJIMA/SUZUKI (2006), Generalization of the run rules for the Shewhart control charts, *Frontiers in Statistical Quality Control*, 8, 207-219 – Lenz/Wilrich (Eds.)



*Alternative control chart methodologies have been suggested, for example, the CUSUM and EWMA schemes.*

*Both of these have excellent small process average shift detection capabilities, as described in Montgomery (1997).*

*However, so far, they do not seem to have achieved widespread application beyond the chemical process industries.*

*This may be due to a perception that the required calculations are too complex for typical shop floor work and/or the usual organizational inertia associated with procedural changes.*

# Do the comparison again

- Measure the performance of Shewhart control charts with runs rules, of CUSUM and of EWMA in terms of the
  - Average Run Length (ARL) – average number of control chart points until signal starting from a standard value,
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  - Average Run Length (ARL) – average number of control chart points until signal starting from a standard value,
  - steady-state ARL – the same while starting after a longer in-control period.
- The charts will be calibrated to exhibit similar in-control behavior!!

## 1 CUSUM

$$Z_0^\pm = 0,$$

$$Z_i^\pm = \max\{0, Z_{i-1}^\pm \pm k\} \quad \text{with } k = \frac{\mu_0 + \mu_1}{2},$$

$$L = \min \{i \in \mathbb{N} : \max\{Z_i^+, Z_i^-\} > h\sigma\}.$$

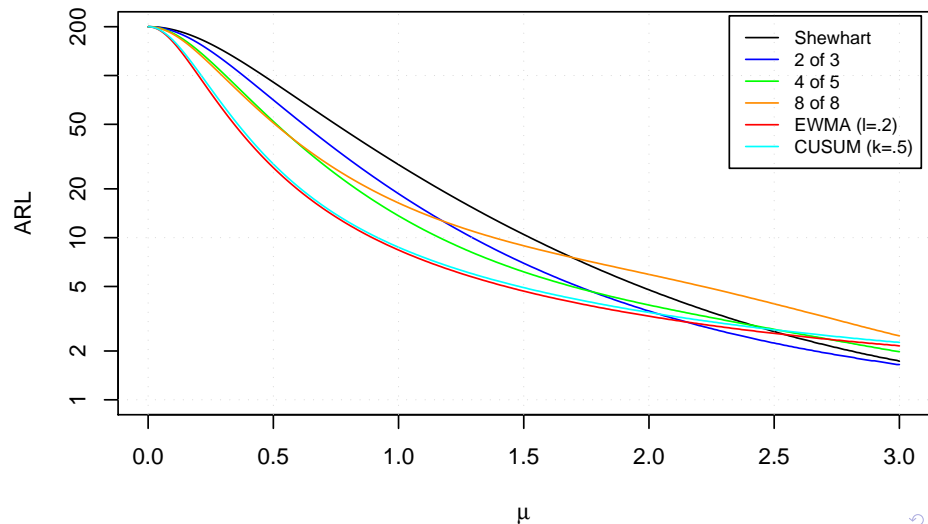
## 2 EWMA

$$Z_0 = \mu_0,$$

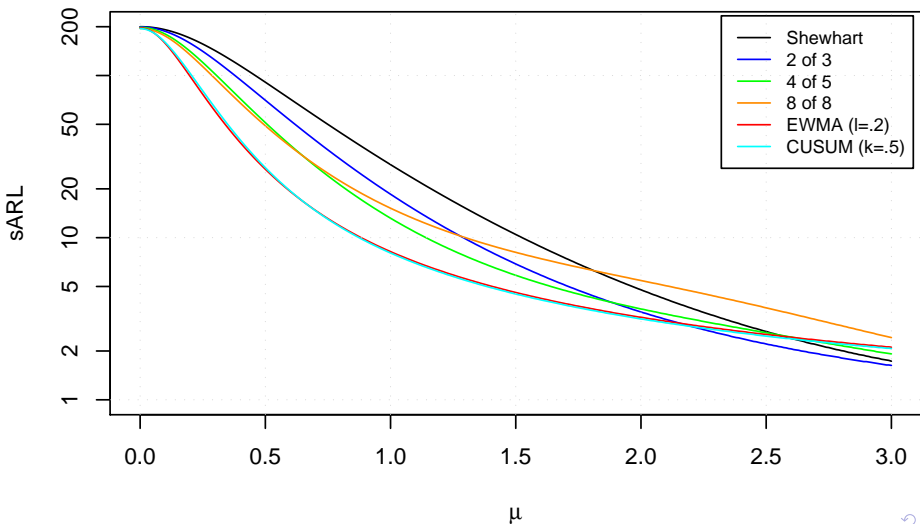
$$Z_i = (1 - \lambda)Z_{i-1} + \lambda X_i \quad \text{with } \lambda \in (0, 1],$$

$$L = \min \left\{ i \in \mathbb{N} : |Z_i - \mu_0| > c \sqrt{\frac{\lambda}{2 - \lambda}} \sigma \right\}.$$

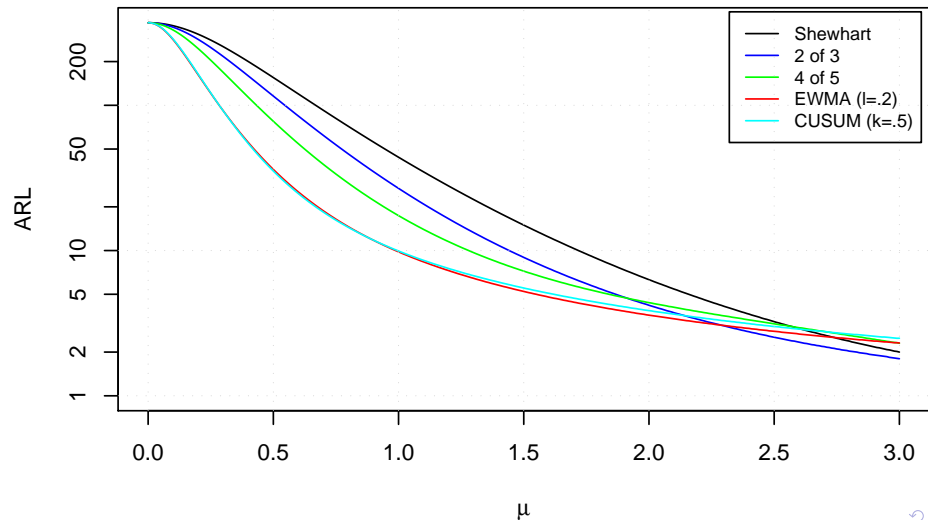
# ARL comparison



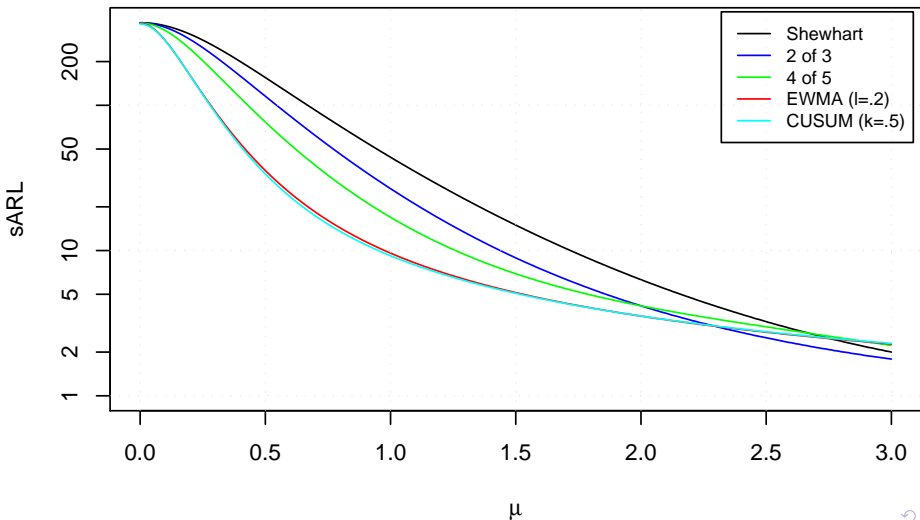
# Steady-state ARL comparison





# ARL comparison



# Steady-state ARL comparison





- Implementation of Champ/Woodall's algorithm (Markov chain) in  and adaptation of the runs rules zones by a common scaling,
- Simple deployment of the Markov chain for getting the steady-state ARL values,
- CUSUM and EWMA ARL and steady-state ARL values are calculated with the `spc` package in  (numerical solution – Nyström method – of an integral equation).

# Why EWMA and not CUSUM (or even Shiryaev-Roberts)?

- EWMA is better known than CUSUM in the semiconductor (and financial) industry,
- EWMA provides an online estimate of the monitored parameter,
- one can facilitate very simple control limits approximation,
- it is easier to sell in practice,
- the performance differences among the three procedures are negligible in practice,
- ...

$$UCL = \mu_0 + c \times \sqrt{\frac{\lambda}{2-\lambda}} \times \sigma_0 \quad \rightarrow \quad c ?$$

- With  sophisticated:

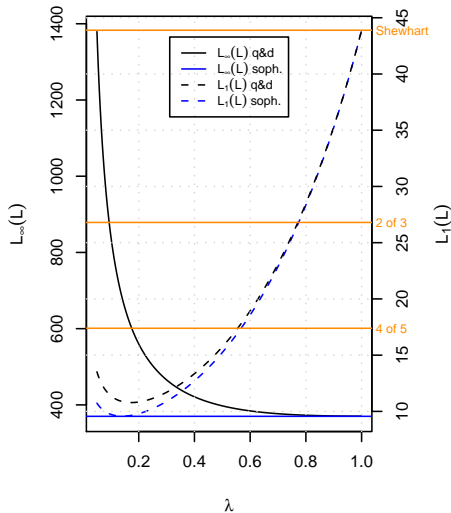
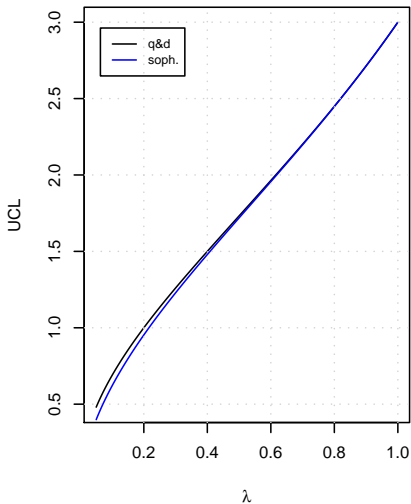
```
library(spc)
xewma.crit(0.2,370,sided="two")
```

delivers

```
      c
2.858961
```

- Or quick and dirty:  $c = 3$

# Quick and dirty vs. sophisticated

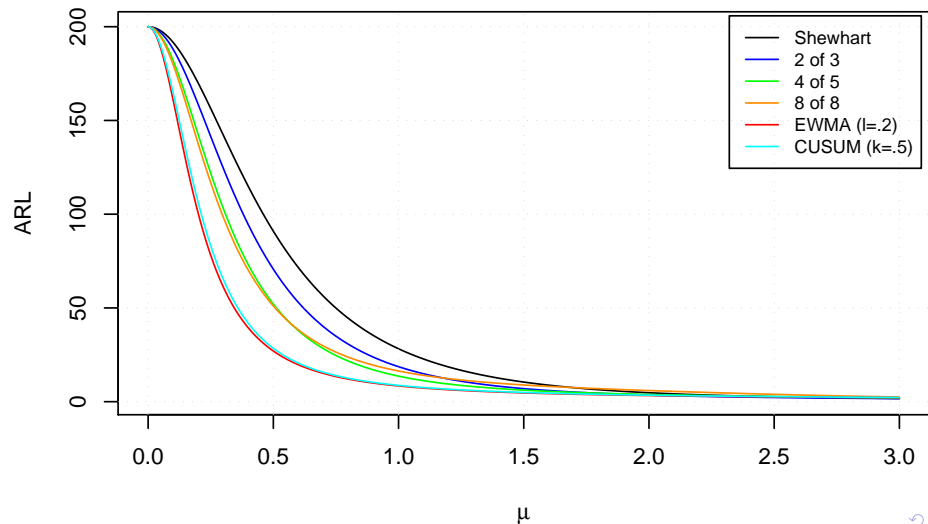


Take the EWMA control chart, because

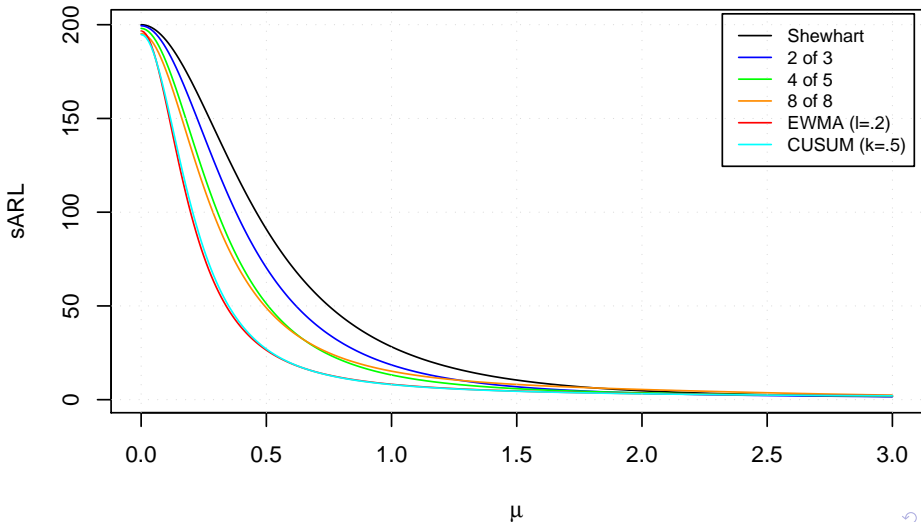
- it behaves as efficient as the optimal ones (CUSUM, SR),
- it beats the Shewhart chart (w/o or w runs rules) for small changes ( $\leq 2\sigma$ ),
- it gets a kind of additional Shewhart limit by applying SPEC limits to the original data,
- it allows to clarify the differences between single event analysis and process shift studies,
- it is easy to deploy and to understand,
- the EWMA smoothing is utilized in close application fields like R2R control in semiconductor industry or volatility forecasting in finance,
- ...

# Backup

# ARL comparison

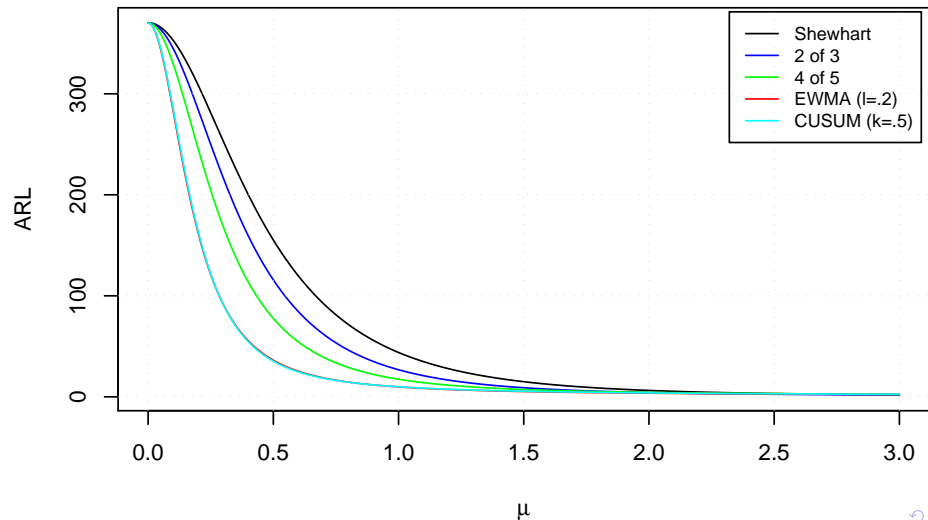


# Steady-state ARL comparison

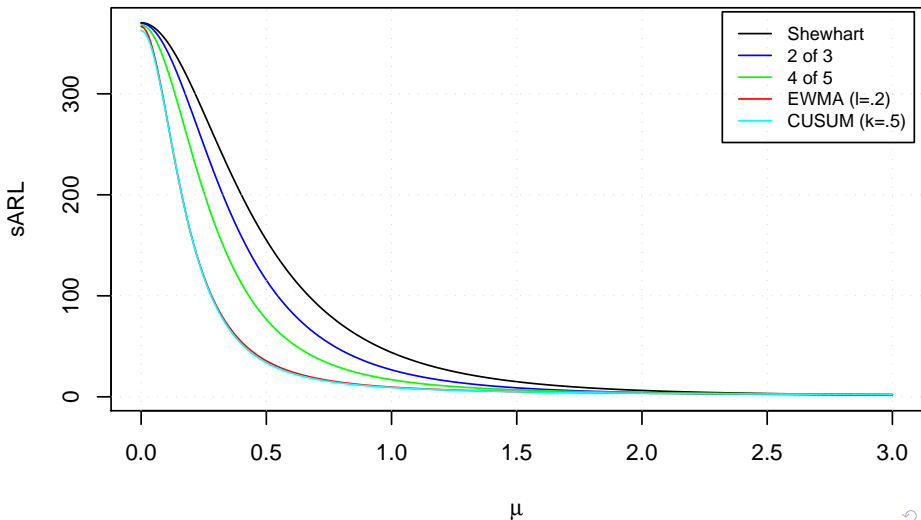




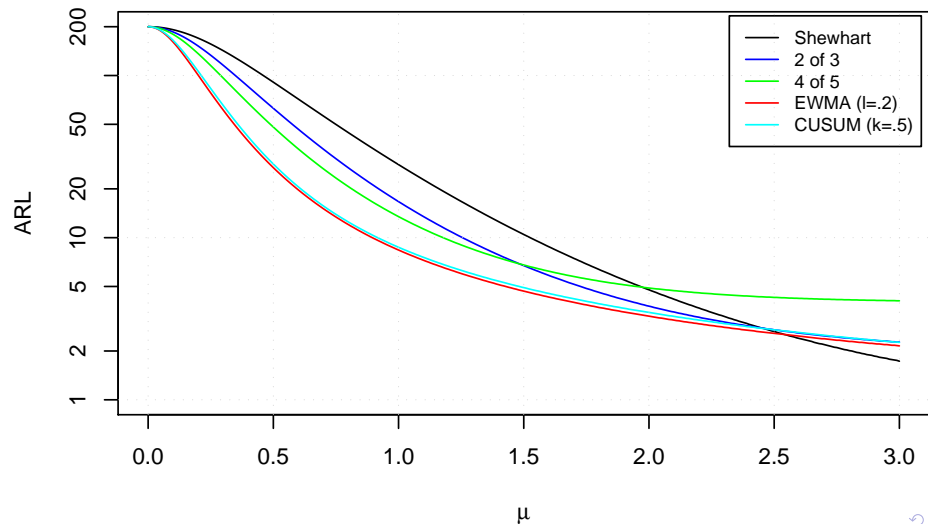
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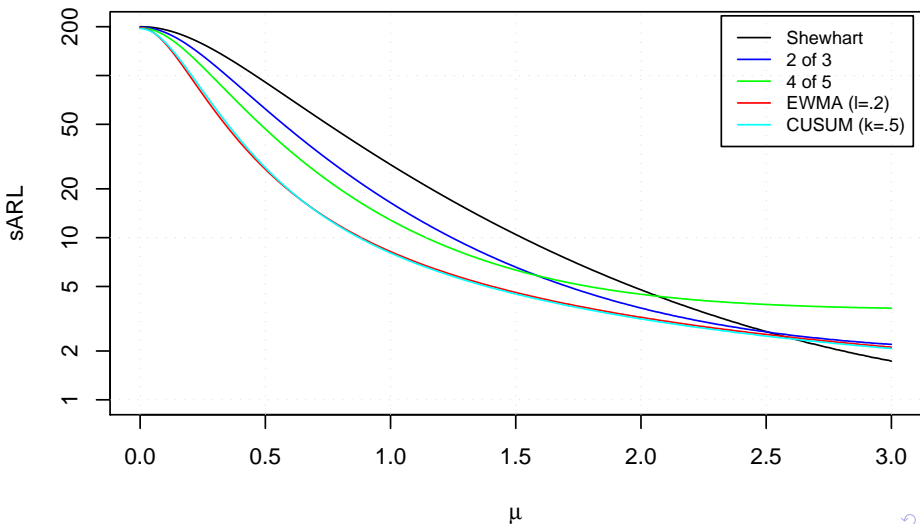
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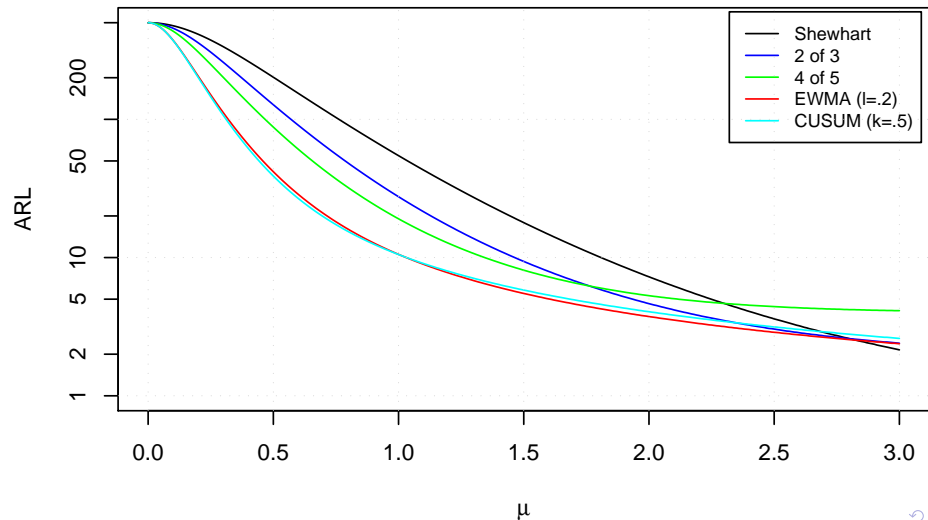
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